

# CORRECTION TO THE PAPER ”SILVER-NANOPARTICLE-BASED ETCH MASK CONTROL FOR SUBWAVELENGTH STRUCTURE DEVELOPMENT”

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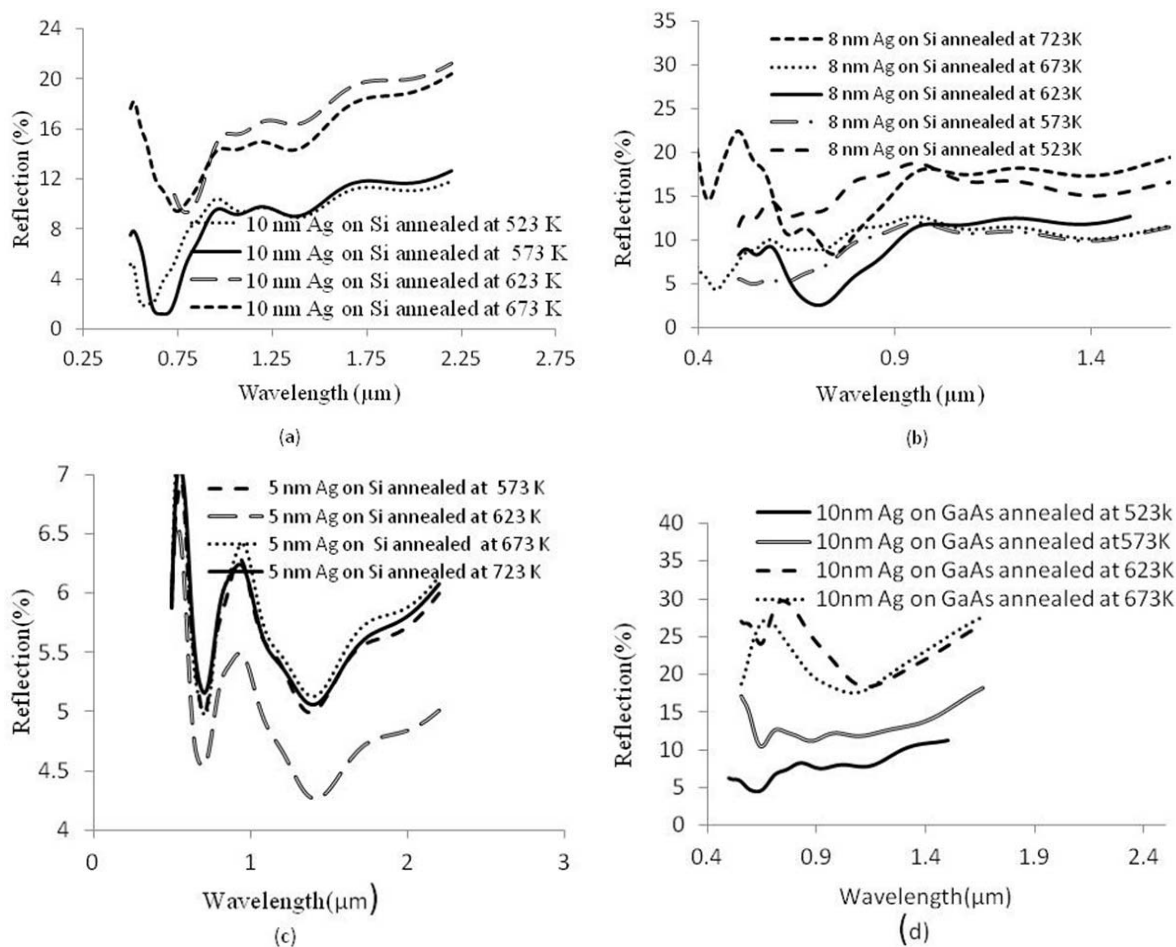
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In the text published in Nanosystems: Physics, Chemistry, Mathematics, 4(3) (2013),  
P. 387–394, figure 6 should be replaced by the following more precise figure



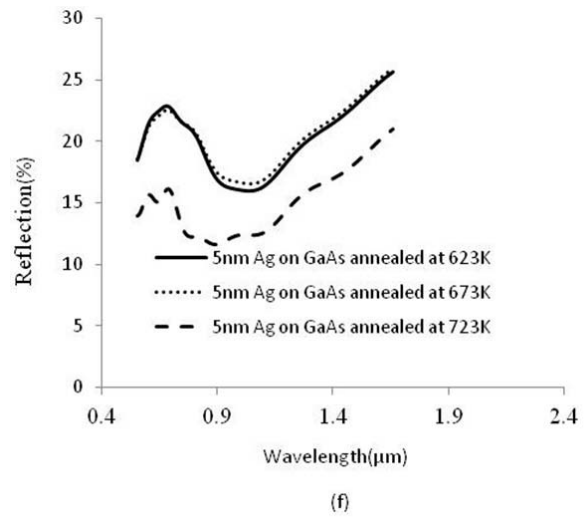
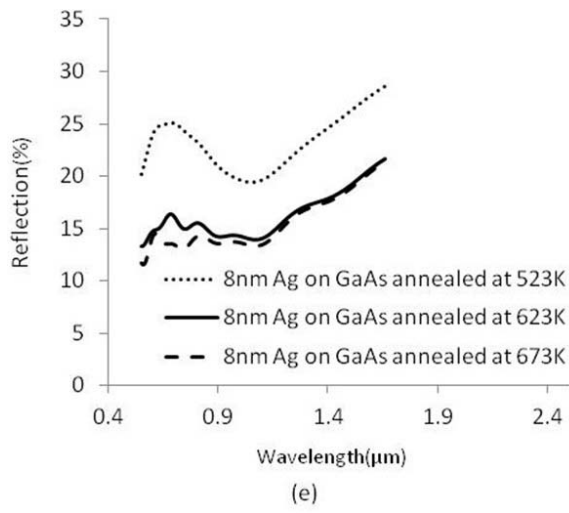


Fig.6. Reflection spectra for various SWG structures developed using 10 nm, 8 nm and 5 nm thick Ag films on Si and GaAs substrates, annealed at different temperatures